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WHAT IS CLAIMED IS:

1. A magnetoresistance element comprising:

a free layer comprising a first ferromagnetic layer and a second ferromagnetic layer that face each other and whose magnetization directions are equal to each other and a nonmagnetic film intervening between the first and second ferromagnetic layers, the free layer being changeable in the magnetization directions on applying a magnetic field;

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a first pinned layer comprising a third ferromagnetic layer that faces the free layer, the first pinned layer retaining a magnetization direction thereof on applying the magnetic field; and

a first nonmagnetic layer intervening between the free layer and the first pinned layer, the nonmagnetic film being made of a material selected from the group consisting of titanium, vanadium, zirconium, niobium, molybdenum, technetium, hafnium, tungsten, rhenium and alloys thereof.

- 2. The magnetoresistance element according to claim 1, wherein an average thickness of the nonmagnetic film falls within a range of 0.1 nm to 10 nm.
- 3. The magnetoresistance element according to claim 1, wherein the nonmagnetic film is made of a material selected from the group consisting of titanium, vanadium, zirconium, niobium, molybdenum,

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technetium, hafnium, tungsten and alloys thereof.

4. The magnetoresistance element according to claim 1, further comprising:

a second pinned layer comprising a fourth ferromagnetic layer that faces the first pinned layer with the free layer interposed therebetween, the second pinned layer retaining a magnetization direction thereof on applying the magnetic field; and

a second nonmagnetic layer intervening between the free layer and the second pinned layer.

- 5. A magnetic memory comprising:
- a word line;

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- a bit line intersecting the word line; and
- a memory cell positioned in an intersection portion of the word and bit lines and including the magnetoresistance element according to claim 1.
 - 6. A magnetic head comprising:

the magnetoresistance element according to claim 1; and

- a support member supporting the magnetoresistance element.
 - 7. A magnetoresistance element comprising:

a free layer comprising a first ferromagnetic layer and a second ferromagnetic layer that face each other and whose magnetization directions are equal to each other and a nonmagnetic film intervening between the first and second ferromagnetic layers, the free

layer being changeable in the magnetization directions on applying a magnetic field;

- a first pinned layer comprising a third ferromagnetic layer that faces the free layer, the first pinned layer retaining a magnetization direction thereof on applying the magnetic field; and
- a first nonmagnetic layer intervening between the free layer and the first pinned layer, a material of the nonmagnetic film being semiconductor or insulator.
- 10 8. The magnetoresistance element according to claim 7, wherein an average thickness of the nonmagnetic film falls within a range of 0.1 nm to 10 nm.
 - 9. The magnetoresistance element according to claim 7, further comprising:
 - a second pinned layer comprising a forth ferromagnetic layer that faces the first pinned layer with the free layer interposed therebetween, the second pinned layer retaining a magnetization direction thereof on applying the magnetic field; and
 - a second nonmagnetic layer intervening between the free layer and the second pinned layer.
 - 10. A magnetic memory comprising:
 - a word line;

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a bit line intersecting the word line; and a memory cell positioned in an intersection portion of the word and bit lines and including

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the magnetoresistance element according to claim 7.

11. A magnetic head comprising:

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the magnetoresistance element according to claim 7; and

- a support member supporting the magnetoresistance element.
 - 12. A magnetoresistance element comprising:
 - a free layer comprising a first ferromagnetic layer and a second ferromagnetic layer that face each other and whose magnetization directions are equal to each other and a nonmagnetic film intervening between the first and second ferromagnetic layers, the free layer being changeable in the magnetization directions on applying a magnetic field;
 - a first pinned layer comprising a third ferromagnetic layer that faces the free layer, the first pinned layer retaining a magnetization direction thereof on applying the magnetic field; and
 - a first nonmagnetic layer intervening between the free layer and the first pinned layer, the nonmagnetic film containing a material selected from the group consisting of titanium, vanadium, zirconium, niobium, molybdenum, technetium, hafnium, tungsten, rhenium, alloys thereof, semiconductors and insulators.
- 25 13. The magnetoresistance element according to claim 12, wherein an average thickness of the nonmagnetic film falls within a range of 0.1 nm to

10 nm.

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- 14. The magnetoresistance element according to claim 12, wherein the nonmagnetic film contains a material selected from the group consisting of titanium, vanadium, zirconium, niobium, molybdenum, technetium, hafnium, tungsten, alloys thereof, semiconductors and insulators.
- 15. The magnetoresistance element according to claim 12, wherein the nonmagnetic film contains a material selected from the group consisting of titanium, vanadium, zirconium, niobium, molybdenum, technetium, hafnium, tungsten, rhenium and alloys thereof.
 - 16. The magnetoresistance element according to claim 12, wherein the nonmagnetic film contains a semiconductor or an insulator.
 - 17. The magnetoresistance element according to claim 12, further comprising:
- a second pinned layer comprising a fourth

 ferromagnetic layer that faces the first pinned layer

 with the free layer interposed therebetween, the second

 pinned layer retaining a magnetization direction

 thereof on applying the magnetic field; and
 - a second nonmagnetic layer intervening between the free layer and the second pinned layer.
 - 18. A magnetic memory comprising:
 a word line;

a bit line intersecting the word line; and a memory cell positioned in an intersection portion of the word and bit lines and including the magnetoresistance element according to claim 12.

19. A magnetic head comprising:

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the magnetoresistance element according to claim 12; and

a support member supporting the magnetoresistance element.